

Amendment to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application. Claims 26 and 29 are herein canceled without prejudice.

Listing of Claims:

1. (Previously presented) A light source comprising:
a light source head;
a first set of poles coupled to the light source head, wherein each pole of the first set of poles has an arc shape; and
a second set of poles coupled to the light source head, the second set of poles interposed within the first set of poles, wherein each pole of the second set of poles has a shape selected from the group consisting of a circular shape and an elliptical shape.
2. (Canceled)
3. (Original) The light source of claim 1, wherein the second set of poles comprises four poles approximately equidistant from each other.
4. – 5. (Canceled)
6. (Previously presented) The light source of claim 3, wherein the first set of poles comprises four poles.

7. (Previously presented) The light source of claim 3, wherein the first set of poles comprises two poles.
8. (Original) The light source of claim 1, wherein the light source is an excimer laser.
9. – 10. (Canceled)
11. (Previously presented) A method comprising:
- locating a first set of poles on a light source, wherein each pole of the first set of poles has an arc shape;
- determining whether a first depth of focus (DOF) tolerance for a first pitch range is acceptable, and if the first DOF tolerance is not acceptable, adjusting the first set of poles;
- locating a second set of poles on the light source, the second set of poles interposed within the first set of poles, wherein each pole of the second set of poles has a shape selected from the group consisting of a circular shape and an elliptical shape; and
- determining whether a second DOF tolerance for a second pitch range is acceptable, and if the second DOF tolerance is not acceptable, adjusting the second set of poles.
12. (Original) The method of claim 11, further comprising determining whether a mask error enhancement factor (MEEF) of the light source is acceptable, and if the MEEF is not acceptable, adjusting the first and second sets of poles.

13. (Original) The method of claim 11, wherein determining whether a DOF tolerance is acceptable comprises using a computer simulation.

14. (Original) The method of claim 11, further comprising using the light source for photolithography.

15. (Canceled)

16. (Previously presented) The method of claim 11, wherein adjusting the first set of poles comprises moving the first set of poles and adjusting a size of the first set of poles, and wherein adjusting the second set of poles comprises moving the second set of poles and adjusting a radius of the second set of poles.

17. (Previously presented) An apparatus comprising:

a hybrid light source including a first set of poles and a second set of poles, wherein each pole of the first set of poles has an arc shape, wherein each pole of the second set of poles has a shape selected from the group consisting of a circular shape and an elliptical shape, wherein the second set of poles is interposed within the first set of poles, and wherein the second set of poles is closer to the center of the hybrid light source than is the first set of poles;

a mask beneath the hybrid light source, the mask including a pattern;

a first lens between the light source and the mask; and

a second lens between the mask and a substrate, the substrate including a layer of photoresist to be patterned with the pattern.

18. (Previously presented) The apparatus of claim 17, wherein the first set of poles is provided to pattern small pitch areas on the substrate, and wherein the second set of poles is provided to pattern large pitch areas on the substrate.

19. (Original) The apparatus of claim 17, wherein the mask is an embedded phase shift mask (EPSM).

20. (Canceled)

21. (Original) The apparatus of claim 17, wherein the first and second sets of poles are adjustable to change characteristics of the hybrid light source.

22. (Original) The apparatus of claim 17, wherein the second set of poles comprises four poles.

23. (Original) The apparatus of claim 22, wherein first set of poles comprises two poles.

24. (Original) The apparatus of claim 22, wherein the first set of poles comprises four poles.

25. (Previously presented) The apparatus of claim 17, wherein the first set of poles is located approximately at an edge of the hybrid light source.
26. – 29. (Canceled)
30. (Previously presented) The light source of claim 1, wherein the first and second sets of poles are adjustable to change characteristics of the light source.
31. (Previously presented) The light source of claim 30, wherein the light source is used for photolithography.
32. (Previously presented) The light source of claim 31, wherein the first and second sets of poles are adjustable to optimize depth of focus (DOF) tolerances.
33. (Previously presented) The light source of claim 1, wherein the second set of poles is closer to the center of the light source head than is the first set of poles.